Deposition and Electrical Characterization of Hafnia ALD Thin Films Using Cp–Based Precursors

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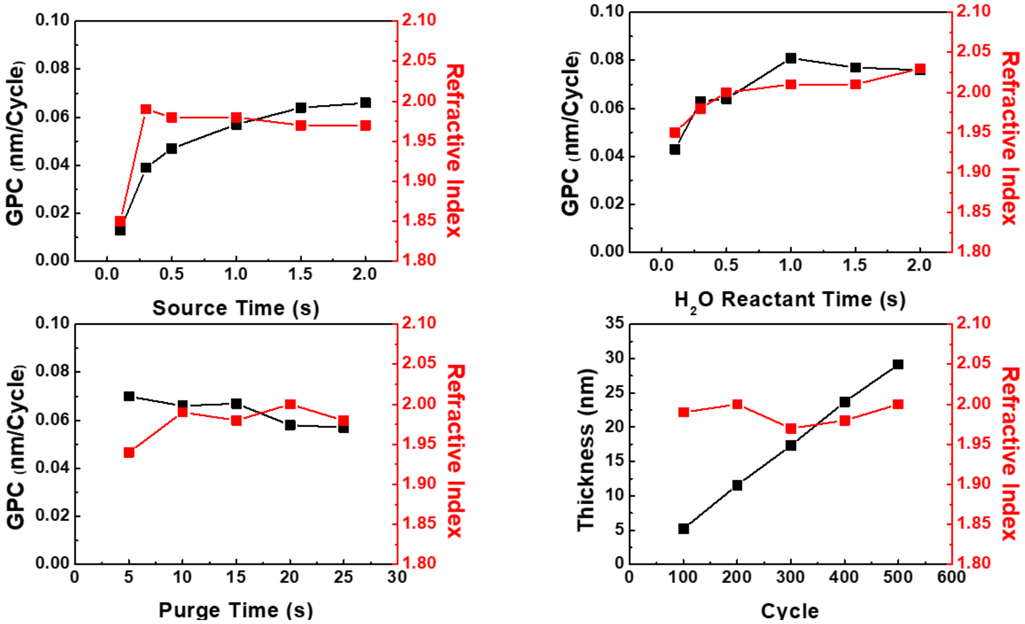
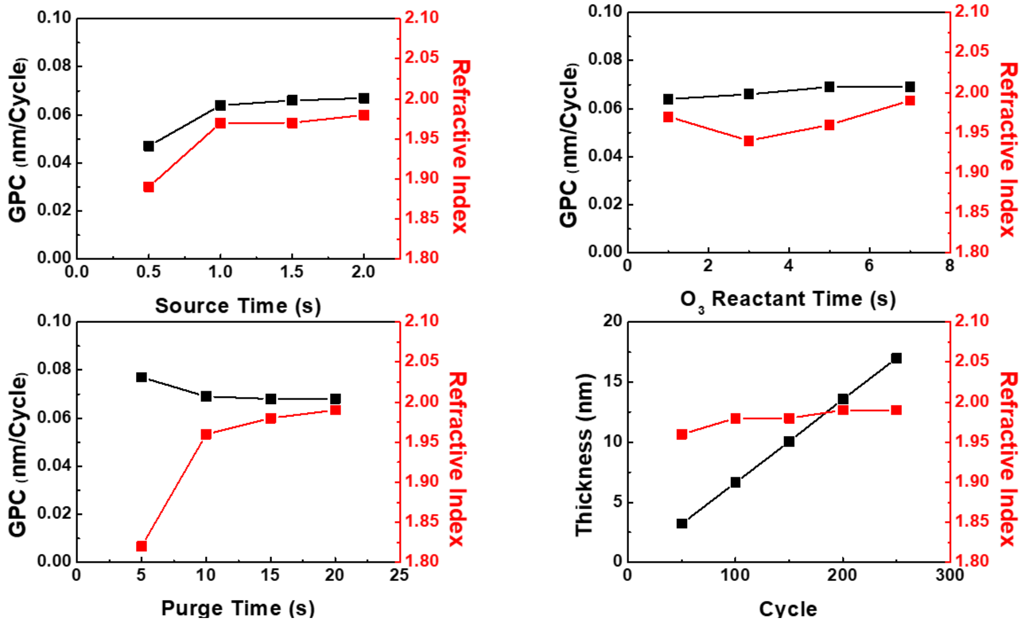


Saturation and Growth Characteristics of Thermal ALD HfO_2 using H_2O Oxidant



Saturation and Growth Characteristics of Thermal ALD HfO_2 using O_3 Oxidant